Attorney Docket No. 040021-0307298 Client Reference: OPP 030894 US

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

GEON-OOK PARK

Application No.:

Confirmation

No:

Filed:

December 19, 2003

Group No.:

Examiner

For:

FORMATION METHOD OF GATE ELECTRODE IN SEMICONDUCTOR

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

APPLICATION DATA SHEET 37 C.F.R. § 1.76

BIBLIOGRAPHIC DATA

1. Applicant information

First applicant: GEON-OOK PARK Citizenship: Republic of Korea

Residence: Seoul, Korea

2. Correspondence information

Correspondence for this application should be addressed as follows:

Customer No.: 00909

3. Application information

Title of Invention: FORMATION METHOD OF GATE ELECTRODE IN SEMICONDUCTOR

Docket number assigned to this application: 040021-0307298

Suggested Classification:

Class:

Subclass:

Technology Center to which subject matter is assigned:

Total number of drawing sheets: 3

Type of application:

Utility

Application is to be published. Suggested drawing figure for publication:

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

4. Representative information

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

5. Foreign priority information

Foreign priority is claimed for this application as follows:

Country: Republic of Korea

Application No.: 10-2002-0082001 Filing Date: December 20, 2002

Status: Pending

6. Assignee information

The assignee(s) of this application is/are:

Anam Semiconductor Inc. 891-10, Daechi-dong, Kangnam-ku Seoul, 135-523 KOREA

Extent of interest of assignee in application: 100%

Date: December 19, 2003

Reg. No.: 28872

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